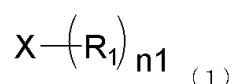


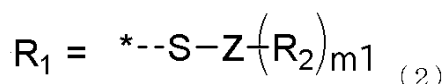
Title of Invention - COMPOSITION FOR FORMING ORGANIC FILM,
METHOD FOR FORMING ORGANIC FILM, PATTERNING PROCESS, AND
COMPOUND

ABSTRACT

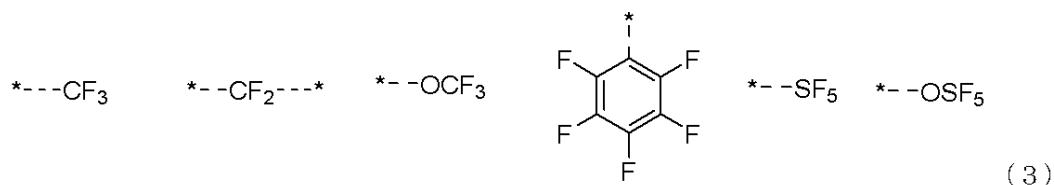
A composition for forming an organic film having excellent film formability, embedding characteristics, suppresses a hump during an EBR process, and has process tolerance when used for a multi-layer resist. The organic film containing (A) a resin or compound (B) a compound represented by formula (1), and (C) a solvent,



wherein R1 is a terminal group represented by formula (2), X is an n1-valent organic group having 2 to 50 carbon atoms, and n1 represents an integer of 2 to 8,



wherein R2 is a monovalent organic group, wherein the monovalent organic group contains at least any of structures having fluorine atoms represented by formula (3), m1 is 1 or 2, wherein when m1 is 1, Z represents a single bond or a divalent organic group optionally containing a heteroatom, and when m1 is 2, Z represents a trivalent organic group optionally containing a heteroatom,



[FIG. 1]